

D. Thin Film Process Technology 분과

2020년 2월 14일(금), 15:45-17:30 / Room K (다이아몬드 I, 6층)

■ [FK3-D] Thin Film Transistors

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FK3-D-1 15:45-16:15	[초청] Geometrically Adaptive Atomically Thin Films Joonki Suh <i>School of Materials Science and Engineering, UNIST</i>
FK3-D-2 16:15-16:30	용액 공정 기반의 이중 게이트 전극 구조의 산화물 Indium-gallium-zinc-oxide TFT의 제작 및 분석 Jeongmin Kim and Jaewook Jeong <i>School of Information and Communication Engineering, Chungbuk National University</i>
FK3-D-3 16:30-16:45	High-Performance ZnO-based Thin Film Transistors with Thin ITO Inserting Layers Suitable for Low Temperature Processing Man-ho Cho and Won-Ju Cho <i>Department of Electronic Materials Engineering, Kwangwoon University</i>
FK3-D-4 16:45-17:00	Mechanically Flexible Vertical-Channel Charge-Trap Memory Thin Film Transistors Using Atomic Layer Deposited Oxide Semiconductors Hyeong-Rae Kim and Sung-Min Yoon <i>Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University</i>
FK3-D-5 17:00-17:15	Fabrication and Characterization of Nanoscale In-Ga-Zn-O Vertical-Channel Thin-Film-Transistors with Sub-130 nm Channel Length Hyun-Joo Ryoo and Sung-Min Yoon <i>Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University</i>
FK3-D-6 17:15-17:30	Annealing Effect on IGZO-Metal Interface Eun Seong Yu, Seok Jun Kang, Jae Geun Woo, In Hye Kang, and Byung Seong Bae <i>School of Electronics and Display Engineering, Hoseo University</i>